

Abstract

Device for treating a surface of a substrate, and a plasma source

5 A device (1) for treating a surface of a substrate (9) comprises a treatment chamber (3) for receiving the substrate therein, and is provided with at least one plasma source (13) for generating a plasma (8) which is connected to the treatment chamber (3). The plasma source (13) is provided with inlet means (11) for admitting at least one reactant into a flow path (95) of the plasma (8). The plasma source (13) comprises at least one
10 cathode (20) and at least one anode (5) between which a system of cascade plates (80) is received. The cascade plates (80) are each provided with a number of passage openings (85) to provide a number of separate flow paths (95) for the plasma (8). Situated preceding the first cascade plate (80) of the system there is a common plasma space (90) which is in open communication with the passage openings (85) in the
15 cascade plates (80) of the system.

Fig. 1